IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of: **Docket No.:** 020732-97.668 (7493)**Applicants:** RATH, Melissa K., et al. Conf. No.: 4823 **Application No.:** 10/792,038 Art Unit: 1752 Date Filed: March 3, 2004 **Examiner:** LE, Hoa Van Title: **Customer No.:** COMPOSITION AND PROCESS FOR 24239 POST-ETCH REMOVAL OF PHOTORESIST AND/OR SACRIFICIAL ANTI-REFLECTIVE MATERIAL DEPOSITED ON A **SUBSTRATE**

RESPONSE TO APRIL 13, 2006 OFFICE ACTION; SUBMISSION OF DECLARATION UNDER 37 CFR §1.131; AND REQUEST FOR A TWO-MONTH EXTENSION UNDER 37 CFR §1.136(a) IN UNITED STATES PATENT APPLICATION NO. 10/792,038

Mail Stop Amendment Commissioner for Patents PO Box 1450 Alexandria, VA 22313-1450

Sir:

Please amend the claims, as set out in the following Section I (the Claims).

Remarks addressing the substance of the April 13, 2006 Office Action are set out in the **Section** II (Remarks) hereof.

A Declaration under 37 CFR §1.131 is included herewith in Appendix A.